

In re: *Kong et al.*
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Listing of Claims:

Claims 1-21 (canceled)

Claim 22 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said reaction vessel is made of quartz.

Claim 23 (canceled)

Claim 24 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said source of electromagnetic radiation comprises an induction coil surrounding said reaction vessel.

Claims 25-48 (canceled)

Claim 49 (currently amended): A chemical vapor deposition system consisting essentially of:

a reactor reaction vessel formed of a material substantially transparent to electromagnetic radiation;
a gas supply system in fluid communication with said reactor reaction vessel;
a source of electromagnetic radiation external to said reaction vessel; and
a susceptor within said reaction vessel, and said susceptor formed of a material that is thermally responsive to electromagnetic radiation, wherein said susceptor ~~being an inverted truncated cone~~ is defined by a plurality of adjacent straight sidewall sections forming a hollow inverted truncated cone with and a plurality of wafer pockets on the inner circumference of said truncated cone, with and wherein the spacing between facing walls sidewall sections is unobstructed and so dimensioned that being small enough for said facing walls sidewall sections to radiantly heat the exposed face surface of a facing

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substrate wafer to substantially the same temperature as said susceptor portion heats a substrate wafer that is in one of said wafer pockets to thereby minimize or substantially eliminate radial and axial temperature gradients across a substrate wafer.

Claim 50 (previously presented): A chemical vapor deposition system according to Claim 49 wherein said susceptor is formed from graphite coated with silicon carbide.